

PATENT ASSIGNMENT

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SUBMISSION TYPE:	NEW ASSIGNMENT
NATURE OF CONVEYANCE:	Release of License Agreement

CONVEYING PARTY DATA

Name	Execution Date
Micronic Laser Systems AB	06/12/2009

RECEIVING PARTY DATA

Name:	ASML Netherlands B.V.
Street Address:	De Run 6501
City:	Veldhoven
State/Country:	NETHERLANDS
Postal Code:	5504 DR

PROPERTY NUMBERS Total: 80

Property Type	Number
Patent Number:	6399261
Patent Number:	6285488
Patent Number:	6687041
Patent Number:	6428940
Patent Number:	6373619
Patent Number:	6504644
Patent Number:	6747783
Application Number:	10776192
Patent Number:	6624878
Patent Number:	6717097
Application Number:	10782863
Patent Number:	6813058
Application Number:	10953560
Patent Number:	6700095
Patent Number:	6645677

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Patent Number:	6816302
Patent Number:	6819490
Application Number:	10238220
Application Number:	09954721
Application Number:	10488353
Patent Number:	6605816
Patent Number:	6618185
Application Number:	10657526
Patent Number:	6903859
Application Number:	10310637
Application Number:	10498590
Application Number:	10498713
Application Number:	10505564
Application Number:	10507554
Application Number:	10510059
Application Number:	11061931
Application Number:	10410874
Application Number:	10462010
Application Number:	11272925
Application Number:	11188876
Application Number:	11206197
Patent Number:	6833854
Patent Number:	6987599
Application Number:	11157043
Application Number:	10634152
Application Number:	10911412
Application Number:	10911218
Patent Number:	6813062
Application Number:	10679701
Application Number:	10704957
Application Number:	10987589
Application Number:	11008566
Application Number:	11030728
Application Number:	11066828
Application Number:	10827530

Application Number:	60675106
Application Number:	10829679
Application Number:	11174568
Application Number:	11061754
Application Number:	60719974
Patent Number:	6624880
Application Number:	10467184
Application Number:	10976548
Patent Number:	6891655
Application Number:	10757351
Application Number:	10977394
Application Number:	10508463
Patent Number:	5486851
Patent Number:	5296891
Patent Number:	5495280
Patent Number:	5936713
PCT Number:	SE0400253
PCT Number:	SE0401161
PCT Number:	SE0401159
PCT Number:	SE0401403
PCT Number:	SE0401638
PCT Number:	SE0401848
PCT Number:	SE0500002
PCT Number:	SE0500269
PCT Number:	SE0500571
PCT Number:	SE0401963
PCT Number:	SE0501050
PCT Number:	SE0500570
PCT Number:	SE0500543
PCT Number:	EP0304283

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NAME OF SUBMITTER: Kathleen M. Bastarache

Total Attachments: 12

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**RELEASE OF INTELLECTUAL PROPERTY LICENSE AGREEMENT COVERING
INTERESTS IN PATENTS**

Reference is made to the Intellectual Property License Agreement, dated December 10, 2004, (the "Agreement") between **Micronic Laser Systems AB (PUBL)**, a limited liability company incorporated in Sweden under registration number 556351-2374, whose registered office is at Nytorpsvägen 9, 183 03 Täby, Sweden ("Micronic"), and **ASML Netherlands B.V.**, a company incorporated under the laws of the Netherlands, whose registered office is at De Run 6501, 5504 DR Veldhoven, the Netherlands, ("ASML"). As of **April 30, 2009**, "Micronic" releases and terminates its security interest in the Intellectual Property Collateral (as defined in the License Agreement) set forth in the **Updated Appendix B to License Agreement** attached hereto.

Dated: June 12, 2009



ASML Netherlands B.V., by its Attorney
C. Hall Swaim, Esq.
Senior Counsel

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**Updated Appendix B to
LICENSE AGREEMENT**

MICRONIC LASER SYSTEMS AB (PUBL), a limited liability company incorporated in Sweden under registration number 556351-2374, whose registered office is at Nytorpsvägen 9, 183 03 Täby, Sweden (“Micronic”);

and

ASML NETHERLANDS B.V., a company incorporated under the laws of the Netherlands, whose registered office is at De Run 6501, 5504 DR Veldhoven, the Netherlands, (“ASML”)

hereby agree to replace the contents of Appendix B of the License Agreement entered by and between Micronic and ASML on December 10, 2004, with the following list of Micronic Background Patents:

Solely owned by Micronic

- 1) “Pattern generator with improved precision” (P00010b)
 - US 6,399,261
 - JP 2000-534915
 - Priority date 02-Mar-1998

- 2) “Improved pattern generator for avoiding stitching errors” (P00010c)
 - US 6,285,488
 - JP 2000/534916
 - EP 99908041.9
 - Priority date 02-Mar-1998

- 3) “Pattern Generator using EUV” (P00010d)
 - US 6,687,041
 - RU 2000124872
 - KR2000-700971 6
 - JP 2000-534917
 - EP 99908042.7
 - CN 99803476.2
 - Priority date 02-Mar-1998

- 4) “Method for pattern generation with improved image quality” (P00010e)
 - US 6,428,940
 - JP 2000-534918
 - Priority date 02-Mar 1998

- 5) "Pattern generator with improved address resolution" (P00010f)
 - US 6,373,619
 - JP 2000-534920
 - EP 99908055.9
 - Priority date 02-Mar-1998
- 6) "Improved modulator design for pattern generator" (P00010g)
 - US 6,504,644
 - JP 2000-534921
 - EP 99908056.7
 - Priority date 02-Mar-1998
- 7) "Improved pattern generator" (P00010a)
 - CN 99803477
 - EP 99908054.2
 - JP 2000-534919
 - KR 451026
 - RU 2232411
 - US 6,747,783
 - US 10/776,192
 - Priority date 02 MAR 1998
- 8) "Laser writer" (P00013)
 - US 6,624,878
 - JP 2000-595202
 - Priority date 21-Jan-1999
- 9) "Data path for high performance pattern generator" (P00015)
 - SE 516914
 - US 6,717,097
 - CN 00812569.4
 - DE 10085017.0
 - JP 2001-522140
 - KR 2002-7003117
 - US 10/782,863
 - Priority date 09-Sep-1999
- 10) "Method and apparatus for personalization of semiconductor" (P00017)
 - SE 522531
 - JP 2001-540838
 - CN 00816201.8
 - EP 00982014.3
 - US 6,813,058
 - KR 2002-7006620
 - US 10/953,560

- Priority date 24-Nov-1999
- 11) "Pattern generator system using a spatial light modulator" (P00018)
 - SE 517550
 - JP 2001-5765341
 - CN 01803213.3
 - KR 7007382
 - US 6,700,095
 - EP 01922177.9
 - Priority date 17-Apr-2000
- 12) "Dual layer reticle blank and manufacturing process" (P00020)
 - US 6,645,677
 - CN 01815867.6
 - DE 10196638.5
 - JP 2002-527860
 - KR 2003-7003950
 - Priority date 18-Sep-2000
- 13) "Improved pattern generator" (P00104)
 - US 6,816,302
 - JP 2002-102101
 - Priority date 04-Apr-2001
- 14) "Homogenization of a spatially coherent radiation beam and reading/writing of a pattern on a workpiece" (P00117)
 - US 6,819,490
 - JP 2003-527781
 - EP 02768252.5
 - Priority date 10-Sep-2001
- 15) "Improved method and apparatus using an SLM" (P00107)
 - US 10/238,220
 - DE 10297208.7
 - JP 2003-527496
 - KR 2004 7003516
 - CN 02821827.2
 - Priority date 12-Sep-2001
- 16) "Graphics engine for high precision lithography" (P00125)
 - US 09/954,721
 - CN 02822476.0
 - KR 2004 7003724
 - JP 2003-527490
 - EP 02768253.3

- Priority date 12-Sep-2001
- 17) "Bonding method" (P00127)
 - SE 523906
 - EP 02798884.9
 - JP 2003-529510
 - US 10/488,353
 - Priority date 20-Sep-2001
- 18) "Dual layer reticle blank and manufacturing process" (P00132)
 - US 6,605,816
 - Priority date 18-Sep-2000
- 19) "Defective pixel compensation method" (P00108)
 - US 6,618,185
 - US 10/657,526
 - EP 02803949.3
 - CN 02823704.8
 - JP 2003-548038
 - KR 2004-7008122
 - Priority date 28-Nov-2001
- 20) "Homogenizer" (P00138)
 - US 6,903,859
 - EP 02793604.6
 - JP 2003-549975
 - KR 2004-7007491
 - CN 02824304.8
 - Priority date 07-Dec-2001
- 21) "Light beam homogenizer" (P00139)
 - US 10/310,637
 - EP 02804376.8
 - CN 02824176.2
 - KR 2004-7007851
 - JP 2003-549830
 - Priority date 07-Dec-2001
- 22) "Improved method and apparatus for image formation" (P00120)
 - EP 02786338.0
 - CN 02824519.9
 - KR 2004-7007850
 - JP 2003-555282
 - US 10/498,590
 - Priority date 10-Dec-2001

- 23) "Method and apparatus for patterning a workpiece" (P00116)
- CN 02825034.6
- EP 02793638.4
- JP 2003-553341
- KR 2004-7008908
- US 10/498,713
- Priority date 14-Dec-2001
- 24) "An image forming method and apparatus" (P00118)
- CN 03804425.0
- EP 03705592.8
- JP 2003-570186
- US 10/505,564
- Priority date 25-Feb-2002
- 25) "Improved addressing method" (P00140)
- CN 03806168.6
- EP 03744576.4
- JP 2003-577037
- US 10/507,554
- Priority date 15-Mar-2002
- 26) "A mask blank and a method for producing the same" (P00135)
- EP 03719227.0
- CN 03807514.8
- KR 2004-7015744
- US 10/510,059
- JP 2003-582503
- Priority date 04-Apr-2002
- 27) "A method and device for coherence reduction" (P00161)
- EP 03791541.0
- US 11/061,931
- JP 2004-532518
- Priority date 02-Sep-2002
- 28) "Method to detect a defective element" (P00162)
- CN 0480001745.4
- KR 2005-7012487
- Priority date 15-Jan-2003
- 29) "Methods and systems for process control of corner feature embellishment" (P00175-1)
- US 10/410,874
- CN 03825015.2
- JP 2005-500104

- KR 2005-7005570
- EP 03748826.9
- Priority date 01-Oct-2002

- 30) "Negative Black" (P00175-2)
 - US 10/462,010
 - CN 03823643.5
 - JP 2005-500105
 - KR 2005-7005456
 - EP 03799230.0
 - US Div 11/272,925
 - Priority date 01-Oct-2002

- 31) "electromagnetic radiation pulse timing control" (P00169)
 - US not yet known
 - EP 04704375.7
 - JP not yet known
 - CN 200480002463.6
 - KR 2005-7012553
 - Priority date 22-Jan-2003

- 32) "SLM addressing method" (P00151)
 - EP 04706912.5
 - JP not yet known
 - KR 2005-7012246
 - US 11/188,876
 - Priority date 31-Jan-2003

- 33) "Pattern generation method" (P00181)
 - EP 04713277.4
 - JP not yet known
 - KR 2005-7012247
 - US 11/206,197
 - Priority date 20-Feb-2003

- 34) "SLM direct writer" (P00137)
 - PCT/SE2004/000253
 - Priority date 28-Feb-2003

- 35) "Method for precision printing of patterns" (P00187)
 - US 6,833,854
 - EP 04748994.3
 - JP not yet known
 - KR 2005-7023861
 - US not yet known

- Priority date 12-Jun-2003
- 36) "Improved pattern generator mirror configurations" (P00188)
 - US 6,987,599
 - CN 0410035361.6
 - JP 2005-269967
 - EP 05013286.9
 - US Div 11/157,043
 - Priority date 01-Mar-2001
- 37) "Method to pattern a substrate" (P00168)
 - US 10/634,152
 - PCT/SE2004/001161
 - US 10/911,412
 - Priority date 04-Aug-2003
- 38) "Enhancement of SLM Lithographic Systems" (P00183)
 - PCT/SE204/001159
 - US 10/911,218
 - Priority date 04-Aug-2003
- 39) "Defective pixel compensation method" (P00108-2)
 - US 6,813,062
 - Priority date 08-Sep-2003
- 40) "Method and device for immersion lithography" (P00191)
 - US 10/679,701
 - PCT/SE2004/001403
 - Priority date 03-Oct-2003
- 41) "Dual layer workpiece masking and manufacturing process" (P00020-2)
 - US Con 10/704,957
 - Priority date 18-Sep-2000
- 42) "Method and device for correcting SLM stamp image imperfections" (P00194)
 - US 10/987,589
 - PCT/SE2004/001638
 - Priority date 12-Nov-2003
- 43) "Phase step mirror" (P00198)
 - US 11/008,566
 - PCT/SE2004/001848
 - Priority date 11-Dec-2003
 - Priority date 15-Dec-2003
 - Priority date 22 Jan 2004

- 44) "Data integrity" (P00199)
– US 11/030,728
– PCT/SE2005/000002
Priority date 08-Jan-2004
- 45) "Improved pattern generator" (P00010a)
– US 10/776,192 (Div)
– CN 99803477
– EP 99908054.2
– JP 2000-534919
– KR 451026
– RU 2232411
– US 6747783
Priority date 02-Mar-1998
- 46) "Data path for high performance pattern generator" (P00015-2)
– US 10/782,863
– Priority date 9-Sep-1999
- 47) "RET for optical maskless lithography" (P00207)
– US 11/066,828
– PCT/SE2005/000269
– Priority date 25-Feb-2004
– Priority date 12-Mar-2004
- 48) "A method for error reduction in lithography" (P00211)
– US 10/827,530
– PCT/SE2005/000571
– Priority date 20-Apr-2004
- 49) "Phase-shifting optical maskless lithography enabling asics at the 65 and 45 nm nodes"
(P00218)
Abandoned because of lack of novelty
- 50) "SLM with actuator made of semiconducting material" (P00220)
– PCT/SE2004/001963
– Priority date 21-Dec-2004
- 51) "Sideways addressing" (P00230)
– US 60/675,106
– PCT/SE2005/010500
– Priority date 27-Apr-2005
- 52) "Improved addressing of an SLM" (P00171)
– US 10/829,679
– PCT/SE2005/000570

- Priority date 22-Apr-2004
- 53) "Hidden hinge mems device" (P00212)
 - US 11/174,568
 - Priority date 6-July-2006
- 54) "Image enhancement technique" (P00224)
 - PCT/SE2005/000543
 - Priority date 15-Apr-2005
- 55) "Lithographic Apparatus and Device Manufacturing Method" (P00228)
 - US 11/061,754
 - Priority date 18-Feb-2005
- 56) "SLM direct writer" (P00237)
 - US not yet known
 - Priority date 21-Dec-2005
- 57) "MDP PG feed forward" (P00247)
 - US 60/719,974
 - Priority date 26-Sep-2005

Jointly owned by Micronic and Fraunhofer (Common Properties)

- 1) "Method and apparatus for microlithography" (P00100)
 - US 6,624,880
 - Priority date 18-Jan-2001
- 2) "Addressing method and apparatus using the same" (P00101)
 - US 10/467,184
 - JP 2002-563057
 - EP 02710598.0
 - Priority date 05-Feb-2001
- 3) "A method and apparatus for spatial light modulation" (P00123)
 - Abandoned
 - Priority date 01-Mar-2001
- 4) "Method using a movable micro-element" (P00144)
 - Abandoned
 - Priority date 15-Mar-2002
- 5) "Method and device for operating a micromechanical element" (P00156)
 - Abandoned
 - Priority date 12-Apr-2002

- 6) "Method and apparatus for controlling deformable actuators" (P00157)
 - EP 02740763.4
 - US not yet known
 - Priority date 04-Jul-2002
- 7) "Device for protecting a chip and method for operating a chip" (P00158)
 - EP 02748681.0
 - JP 2004-501310
 - US 10/976,548
 - Priority date 29-Apr-2002
- 8) "High energy, low energy density, radiation-resistant optics used with micro-electromechanical devices" (P00147)
 - US 6,891,655
 - JP 2004-564602
 - CN 0380107933.0
 - KR 2005-7012488
 - EP 03768474.3
 - Priority date 02-Jan-2003
- 9) "Method to detect a defective element" (P00162)
 - US 10/757,351
 - JP not yet known
 - EP 04702111.8
 - Priority date 15-Jan-2003
- 10) "Method and apparatus for controlling exposure of surface of a substrate" (P00182)
 - PCT/EP03/04283
 - US 10/977,394
 - JP 2004-571029
 - EP 03727355.4
 - Priority date 24-Apr-2003

Jointly owned by Micronic and ASML

- 1) "Method and apparatus for printing large data flows" (P00152)
 - TW NI-182597
 - CN 03806638.6
 - EP 03745053.3
 - KR 2004-7014867
 - SG 200404764-3
 - US 10/508,463
 - JP 2003-579009
 - HK 05108461.8
 - Priority date 21-Mar-2002

- 2) "Lithographic apparatus and device manufacturing method" (P00228)
- US 11/061,754
- Priority date 18-Feb-2005-05-31

Solely owned by Fraunhofer (FHG IP)

- 1) US 5,486,851
2) US 5,296,891
3) US 5,495,280
4) US 5,936,713
5) DE 10046518
6) 98/34027

MICRONIC LASER SYSTEMS AB (PUBL)

ASML NETHERLANDS B.V.

Sven Löfquist
Title: President & CEO

A.J.M. van Hoef
Title: VP and Chief IP Counsel